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Recommended Citation

Dennison, JR; Wilson, Gregory; and Gillespie, Jodie C., "Temperature-Dependent Radiation Induced Conductivity of Diverse Highly Disordered Insulating Materials" (2012). Four Corner Sections Meeting American Physical Society. *Presentations.* Paper 2. https://digitalcommons.usu.edu/mp_presentations/2

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APS Four Corner Sections Meeting

New Mexico Tech Socorro, NM October 26 & 27, 2012

Temperature-Dependent Radiation Induced Conductivity of Diverse Highly Disordered Insulating Materials

J.R. Dennison, Gregory Wilson and Jodie Gillespie



Materials Physics Group Physics Department, Utah State University

Complementary Responses to Radiation



Conduction Band σος ϵ_{CB} Modified Joblonski diagram ϵ_{ST} Intersystem Crossings ΛΛΛ, hv≈ε_{cB}-ε_{DT} • VB electrons excited into CB by the high energy incident electron radiation. • They relax into shallow trap (ST) ε_{DT} states, then thermalize into lower available long-lived ST. • Three paths are possible: High Energy relaxation to deep traps (DT), with e⁻ concomitant photon emission; (ii) radiation induced conductivity (RIC), Non-radiative processes or e⁻h⁺ recombination with thermal re-excitation into the CB; or (iii) non-radiative transitions or e-h+ ε_{VB} recombination into VB holes. Valence Band

(i)





Uniform Trap DensityExponential Trap Density $\Delta(T) \rightarrow 1$ $\Delta(T) \rightarrow \frac{T_c}{T+T_c}$ $k(T) \rightarrow k_{RICo}$ $k(T) \rightarrow k_{RIC1} \left[2 \left(\frac{m_e k_B T}{2\pi\hbar^2} \right)^{3/2} \left(\frac{m_e^* m_h^*}{m_e m_e} \right)^{3/4} \right]^{\frac{T}{T+T_c}}$ $\sigma_{RIC}(T, D) = k_{RIC}(T) \cdot D^{\Delta(T)}$

RIC Depends on Power Deposited



• The RIC versus radiation dose rate for polyethylene terephthalate (Mylar) [Campbell].

• The exponential fit over 10 orders of magnitude for five different studies implies that RIC is largely independent of the beam energy and type of radiation used.

• Only the amount of energy being deposited determines the magnitude of RIC.



Curve Segment	Type of Radiation	Energy	Dose Rate	Mode
1 2 3 4	X-rays X-rays γ-rays pulse reactor	250 keV 15 to 30 keV 1.17 and 1.33 MeV	0.13 rad/s 1 to 400 rad/s 200 to 3500 rad/s	steady state steady state steady state
5	neutrons and γ -rays electrons	mixed 30 MeV	6.5×10^4 to 3.8×10^6 R/s 5 $\times 10^7$ to 7 $\times 10^9$ rad/s	13 ms pulses 4.5 μ s pulses



DOSE RATE is the deposited power per unit mass is:

$$\dot{D}(J_b, E_b) = \frac{E_b J_b [1 - \eta(E_b)]}{q_e \rho_m} \times \begin{cases} [1/L] & ; R(E_b) < L \\ [1/R(E_b)] & ; R(E_b) > L \end{cases}$$

which is proportional to incident electron absorption:

- Incident areal power density, $(J_b \cdot E_b)/q_e$
- Energy-dependant correction for unabsorbed quasielastic backscattered electrons, $[1-\eta(E_b)]$
- For biased samples, or when excess charge is stored in the trap states, a surface voltage V_s results and E_b is replaced everywhere by the landing energy, $[E_b - q_e \cdot V_s]$
- Absorbing mass, $m_{absorb} = \rho_m \cdot (Beam Area \cdot Penetration Depth)$
- Only a fraction of the incident power, $[L / R(E_b)]$, when range exceeds sample thickness







RIC Is Depth Dependant





RIC Dependence on Temperature





Kapton[™] (polyimide)

Family of curves of ρ_{RIC} vs dose rate at various temperatures. Fits are simple power law fits.

 $\sigma_{RIC}(T,D) = k_{RIC}(T) \cdot D^{\Delta(T)}$

RIC Dependence on Temperature







$$\sigma_{RIC}(T,D) = k_{RIC}(T) \cdot D^{\Delta(T)}$$

- ••• Yagahi, 1963 Data
- ---- Exponential FIt
- Power Law Fit
- Fowler, 1956 Data
- USU Data

T dependence of RIC coefficients k (Left) and Δ (Right) with k_o= 1.5-10⁻¹⁶ (Ω -cm-Rad/s)⁻¹, k₁= 7.0-10⁻²⁹ (Ω -cm-Rad/s)⁻¹ and T_c = 230 K.



Fit to Delta at RT
Other Data Sets

🔺 🔺 USU Data

1000 / T (K)



Luminescent intensity, I_{γ} , scales with incident current density J_b , beam energy E_b , temperature T, and photon wavelength λ as

$$I_{\gamma}(J_b, E_b, T, \lambda) \propto \dot{D}(J_b, E_b) \left[\frac{1}{\dot{D} + \dot{D}_{sat}} \left(\frac{\varepsilon_{ST}}{k_B T} \right) \right] \left\{ \mathbb{A}_f(\lambda) [1 + \mathbb{R}_m(\lambda)] \right\}$$

which is proportional to:

• Number of electrons in ST, thermalized from CB electrons

> Trapping rates proportional to number of electrons excited in to CB which is proportional to dose rate

> Retention rates leads to saturation at high charge, related to dose and T-dependent \dot{D}_{sat} from RIC [5]

- Number of available DT states, dependant on space charge and T
- Emitted photon absorption
 - Proportional to A_f, the optical absorption coefficient of the coating

> Enhanced by a factor $[1 + \mathbb{R}_m(\lambda)]$, to account for reflection from the metallic layer

Summary of Cathodoluminescence





Peak amplitudes of four peaks as a function of sample temperature, with baseline subtracted and normalized to maximum amplitudes. This verified the T-dependent behavior observed in the SLR images.

Closed-System Helium Refrigerator Sample Stage Mounting





Sample Square Holder Assembly Diagram





RIC Measurements





RIC Results





Ending with a Bang!!!













RIC in Thin Film Disordered SiO₂ is:

- I. Proportional (nearly) to Dose Rate
- II. Weakly (and roughly linearly) T-dependent
- **III.** Complementary with cathodoluminescence
- **IV. RIC** has rapid time dependance
- V. Suggests a nearly linear density of localized states (shallow traps)

Acknowledgements



Support & Collaborations

Air Force Research Lab

NASA/JWST (GSFC)

National Research Council



B42 Amberly E. Jensen

Dependence of Electron Beam Induced Luminescence of SiO₂ Optical Coatings on Energy, Flux, Temperature and Thickness

B4 4 JR Dennison

Comparison of Radiation Induced Conductivities at Low Temperature

B47 Greg Wilson

Power and Charge Deposition in Multilayer Dielectrics undergoing Monoenergetic Electron Bombardment

D1 40 Allen Anderson Electrostatic Discharge Properties of Fused Silica Coatings

















New Sample Square Holder







New Sample Mount-Au/Kapton Sample







New Sample Mount-Broken Silica Sample

New Sample Square Holder







New Sample Mount Rear Views





New Sample Square Holder Assembly Diagram





Cryostat RIC Equivalent Circuit--Full Circuit





11/2/2012

USU JWST: Fused Silica and ESD



USU/AFRL RIC Cryostat System Block Diagram

JR Dennison Kent Hartley Ver. 1.0 10/01/12 Ver. 1.1 10/02/12 Ver. 1.2 10/11/12





USU Experimental Capabilities



Absolute Yields

- SEE, BSE, emission spectra , (<20 eV to 30 keV)
- •Angle resolved electron emission spectra
- Photoyield (~160 nm to 1200 nm)
- Ion yield (He, Ne, Ar, Kr, Xe; <100 eV to 5 keV)
- Cathodoluminescence (200 nm to 5000 nm)
- No-charge "Intrinsic" Yields
- T (<40 K to >400 K)



- Conductivity (<10⁻²² [ohm-cm]⁻¹)
- Surface Charge (<1 V to >15 kV)
- ESD (low T, long duration)
- Radiation Induced Conductivity (RIC)
- Multilayers, contamination, surface modification
- Radiation damage
- Sample Characterization

End with a Bang





Model for Luminescence Intensity in Fused Silica



Fig. 2. Qualitative two-band model of occupied densities of state (DOS) as a function of temperature during cathodoluminescence. (a) Modified Joblonski diagram for electron-induced phosphorescence. Shown are the extended state valence (VB) and conduction (CB) bands, shallow trap (ST) states at ε_{ST} within $\sim k_B T$ below the CB edge, and two deep trap (DT) distributions centered at $\varepsilon_{DT} = \varepsilon_{red}$ and $\varepsilon_{DT} = \varepsilon_{blue}$. Energy depths are exaggerated for clarity. (b) At $T \approx 0$ K, the deeper DT band is filled, so that there is no blue photon emission if $\varepsilon_{blue} < \varepsilon_{eff}$. (c) At low T, electrons in deeper DT band are thermally excited to create a partially filled upper DT band (decreasing the available DOS for red photon emission) and a partially empty lower DT band (increasing the available DOS for blue photon emission) and a partially empty lower DT band increase blue photon emission. Radiation induced

(2)

$$V_{\gamma}(J_b, E_b, T, \lambda) \propto \dot{D}(J_b, E_b) \left[\frac{1}{\dot{D} + \dot{D}_{sat}} \left(\frac{\varepsilon_{ST}}{k_B T}\right)\right] \left\{ \mathbb{A}_f(\lambda) [1 + \mathbb{R}_m(\lambda)] \right\}$$
(1)

where dose rate \dot{D} (absorbed power per unit mass) is given by

$$\dot{D}(J_b, E_b) = \frac{E_b J_b [1 - \eta(E_b)]}{q_e \rho_m} \times \begin{cases} [1/L] & ; \ R(E_b) < L \\ [1/R(E_b)] & ; \ R(E_b) > L \end{cases}$$



Fig. 3.Range and dose rate of disordered SiO_2 as a function of incident energy using calculation methods and the continuous slow-down approximation described in [5].

LANL Seminar

MATERIALS PHYSICS GROUP

Measured Cathodoluminescence Intensity in Fused Silica





Fig. 1. Optical measurements of luminescent thin film disordered SiO₂ samples. **(a)** Three luminescence UV/VIS spectra at decreasing sample temperature. Four peaks are identified: red (~645 nm), green (~500 nm), blue (~455 nm) and UV (275 nm). **(b)** Peak amplitudes as a function of sample temperature, with baseline subtracted and normalized to maximum amplitudes. **(c)** Peak wavelength shift as a function of sample temperature. **(d)** Total luminescent radiance versus beam current at fixed incident energy fit by (1). **(e)** Total luminescent radiance versus beam energy at fixed 10 nA/cm² incident flux for epoxy-resin M55J carbon composite (red; linear fit), SiO₂ coated mirror (green; fit with (1)), and



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Fused Silica--Cryo ESD Breakdown Sites





FS 4 Post-Breakdown



FS 4 Breakdown Site Close-up





Kapton Sheet Under FS 4 Kapton Pad Over FS 4

Run 10 Rear Electrode Current Analysis





APS 4 Corners